



$p-n$ Junction

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3.5.3 Transient Behavior (رفتار گذرا)

❖ For switching applications, the forward-to-reverse-bias transition must be nearly abrupt and the transient time should be short.

❖ Figure 20a shows a simple circuit where a forward current I_F flows through a $p-n$ junction.

❖ At time $t = 0$, switch S is suddenly thrown to the right and an initial reverse current

$I_R \cong V/R$ flows.

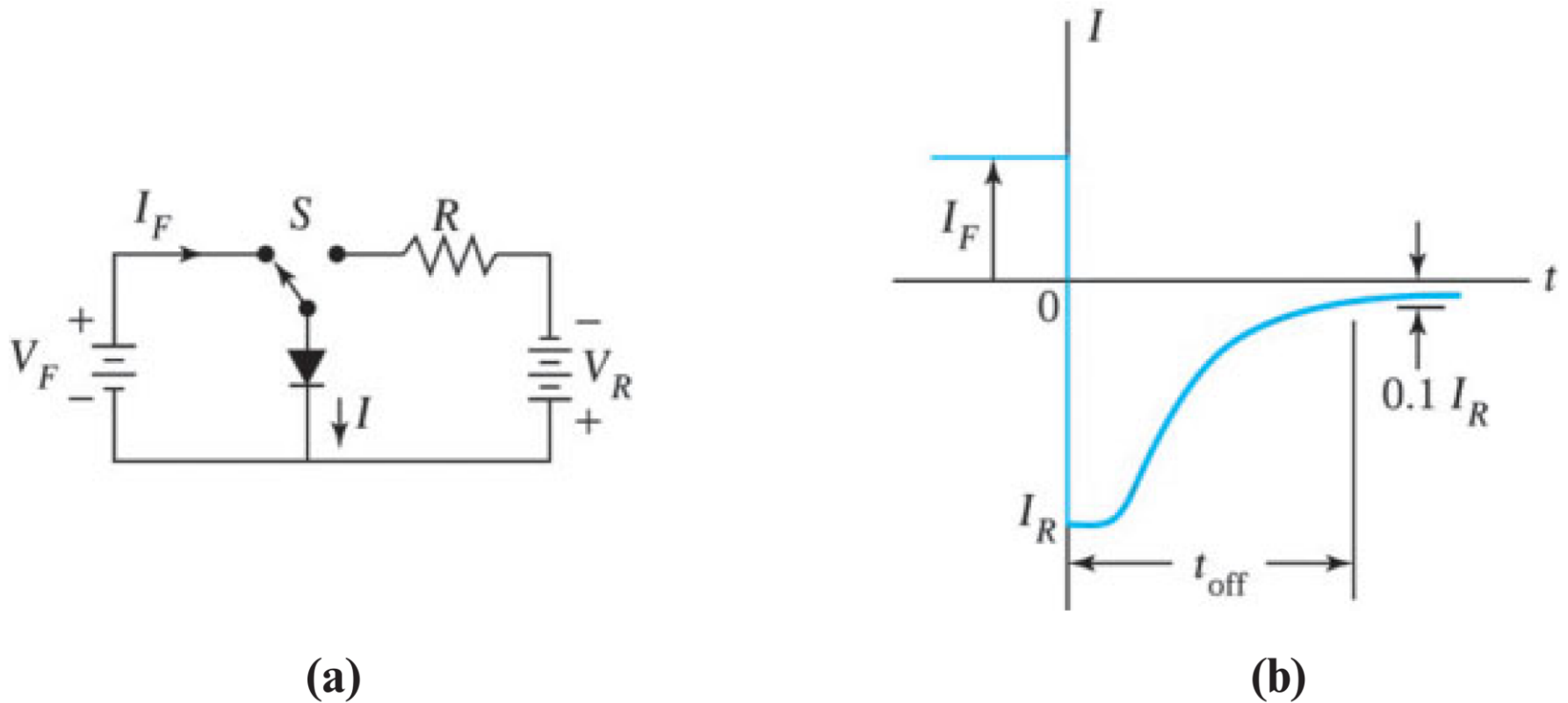


Fig. 20 Transient behavior of a p - n junction. (a) Basic switching circuit. (b) Transient response of the current switched from forward bias to reverse bias.

❖ The transient time t_{off} , plotted in Fig. 20b, is the time required for the current to reach 10% of the initial reverse current IR .

❖ The transient time may be estimated as follows.

❖ Under the forward-bias condition, the stored minority carriers in the n -region for a

p^+-n junction is given by Eq. 76:

$$Q_p = \frac{L_p^2}{D_p} J_p(x_n) = \tau_p J_p(x_n). \quad (76)$$

$$Q_p = \tau_p J_p = \tau_p \frac{I_F}{A}, \quad (79)$$

❖ where I_F is the total forward current and A is the device area.

❖ If the average current flowing during the turn-off period is $I_{R,ave}$, the turn-off time is

the length of time required to remove the total stored charge Q_p :

$I_{R,ave}$ میانگین جریان معکوس
مطابق شکل ۲۰ بین جریان
ماکزیمم IR و IR 10% می باشد

$$t_{off} \cong \frac{Q_p A}{I_{R,ave}} = \tau_p \left(\frac{I_F}{I_{R,ave}} \right). \quad (80)$$

❖ Thus the turn-off time depends on both the ratio of forward to reverse currents and the lifetime of the minority carriers.

- ❖ The result of a more precise turn-off time calculation taking into account the time-dependent minority-carrier diffusion problem is shown in Fig. 21.
- ❖ For fast-switching devices, we must reduce the lifetime of the minority carriers.
- ❖ Therefore, we usually introduce recombination-generation centers that have energy levels located near mid-bandgap, such as gold in silicon.

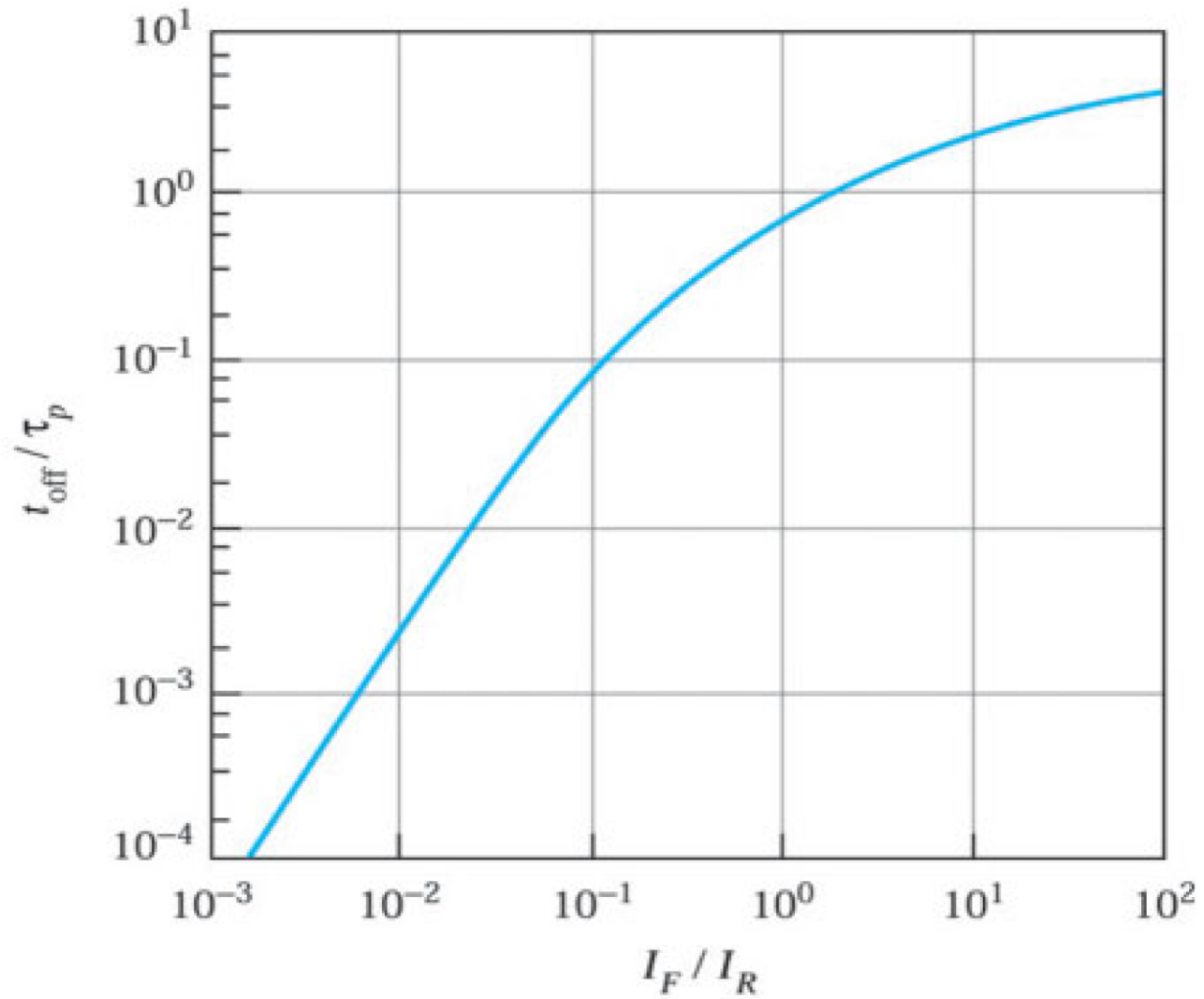


Fig. 21 Normalized transient time versus the ratio of forward current to reverse current.

➔ 3.6 JUNCTION BREAKDOWN

- ❖ When a sufficiently large reverse voltage is applied to a p–n junction, the junction breaks down and conducts a very large current.
- ❖ Although the breakdown process is not inherently (مخرب) destructive (ذاتاً), the maximum current must be limited by an external circuit to avoid excessive (بیش از) junction heating (اندازه).
- ❖ Two important breakdown mechanisms are the tunneling effect and avalanche multiplication (تکثیر بهمینی).

- ❖ We consider the first mechanism briefly and then discuss avalanche multiplication in detail, because avalanche breakdown imposes an upper limit on the reverse bias for most diodes.
- ❖ Avalanche breakdown also limits the collector voltage of a bipolar transistor (Chapter 4) and the drain voltage of a MOSFET (Chapters 5 and 6).
- ❖ In addition, the avalanche multiplication mechanisms can generate microwave power, as in an IMPATT diode (Chapter 8), and detect optical signals, as in an avalanche photodetector (Chapter 10).

3.6.1 Tunneling Effect

- ❖ When a high electric field is applied to a $p-n$ junction in the reverse direction, a valence electron can make a transition from the valence band to the conduction band, as shown in Fig. 22a.
- ❖ This process, in which an electron penetrates through the energy bandgap, is called tunneling.

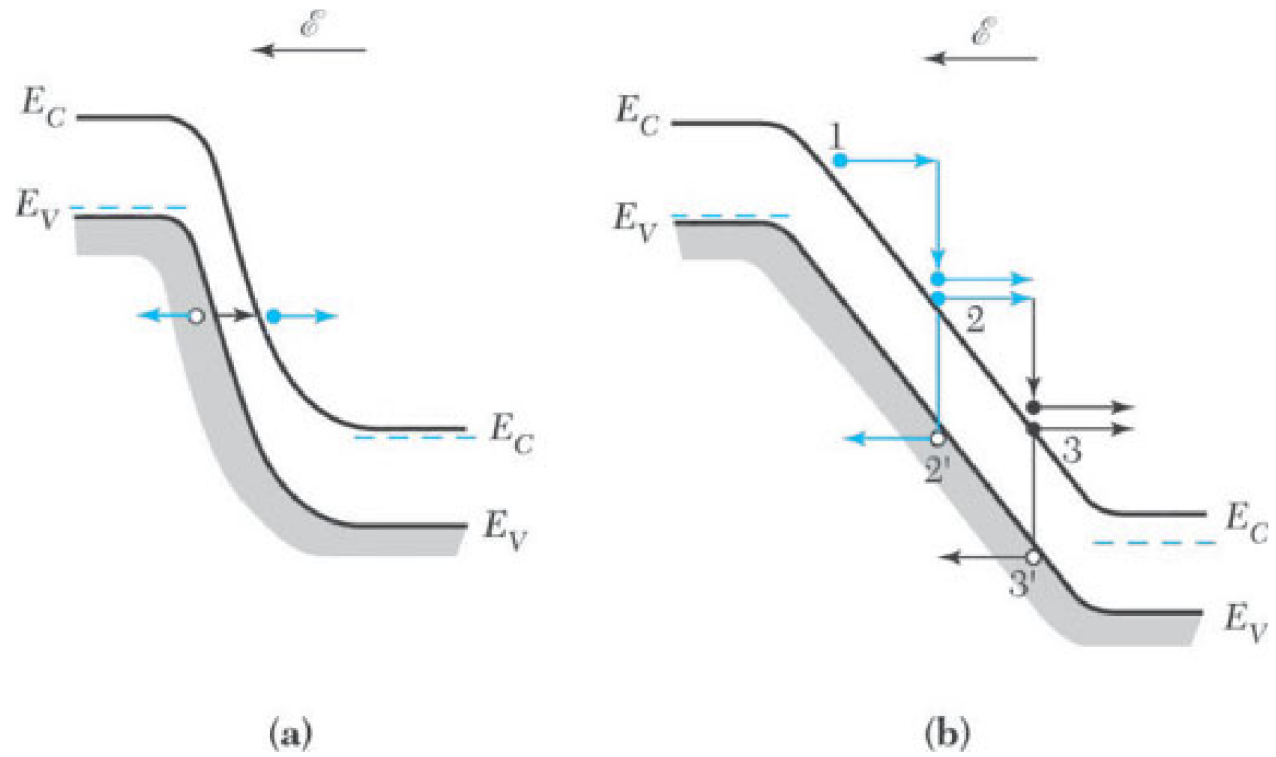


Fig. 22 Energy band diagrams under junction-breakdown conditions. (a) Tunneling effect. (b) Avalanche multiplication.

- ❖ Tunneling occurs only if the electric field is very high.
- ❖ The typical field for silicon and gallium arsenide is about 10^6 V/cm or higher.
- ❖ To achieve such a high field, the doping concentrations for both p - and n -regions must be quite high ($> 5 \times 10^{17}$ cm⁻³).
- ❖ The breakdown mechanisms for silicon and gallium arsenide junctions with breakdown voltages of less than about $4E_g/q$, where E_g is the bandgap, are the result of the tunneling effect.

- ❖ For junctions with breakdown voltages in excess of $6E_g/q$, the breakdown mechanism is the result of avalanche multiplication.
- ❖ At voltages between 4 and $6E_g/q$, the breakdown is due to a mixture of both avalanche multiplication and tunneling.

3.6.2 Avalanche Multiplication

- ❖ The avalanche multiplication process is illustrated in Fig. 22b.
- ❖ The p–n junction, such as a $p^+–n$ one-sided abrupt junction with a doping concentration of $N_D \cong 10^{17} \text{ cm}^{-3}$ or less, is under reverse bias.
- ❖ A thermally generated electron in the depletion region (designated by 1) gains kinetic energy from the electric field.

- ❖ If the field is sufficiently high, the electron can gain enough kinetic energy that on collision with an atom, it can break the lattice bonds, creating an electron-hole pair (2 and 2').
- ❖ The newly created electron and hole both acquire kinetic energy from the field and create additional electron-hole pairs (e.g., 3 and 3').
- ❖ These in turn continue the process, creating other electron-hole pairs.
- ❖ This process is therefore called avalanche multiplication.